

*AS*

**Please replace the paragraph beginning on page 12, line 4 with the following rewritten paragraph:**

From the viewpoint of data processing, it is convenient to measure irregularities or undulations of the polishing surface 12a radially across the polishing surface 12a. However, in the present embodiment, since the sensor 13 is mounted on the dresser head 11a that is angularly movable about a center O of the dresser 11 (see FIG. 3), the sensor 13 is moved along a curved line Lc around the center O, as shown in FIG. 3, rather than along a simple straight line radially across the polishing surface 12a.

**IN THE CLAIMS:**

**Please cancel claim 7.**

**Please amend claims 1-6 as follows:**

*AS*

*AB*

*AB*

1. (Amended) A polishing apparatus for polishing a workpiece, said polishing apparatus comprising:
  - a polishing table having a polishing surface;
  - a top ring for holding a workpiece and pressing the workpiece against said polishing surface;
  - a dresser for dressing said polishing surface; and
  - a sensor for observing a property of said polishing surface on said polishing table while said polishing surface is being dressed by said dresser, said sensor being mounted on said dresser.
2. (Amended) The polishing apparatus according to claim 1, wherein said sensor is for observing irregularity or undulation of said polishing surface.
3. (Amended) The polishing apparatus according to claim 1, further comprising a display device for displaying the property of said polishing surface observed by said sensor.
4. (Amended) The polishing apparatus according to claim 1, wherein said sensor is vertically movable independently of said top ring or said dresser.

5. (Amended) The polishing apparatus according to claim 1, wherein said sensor is to observe a property of said polishing surface over an area that is larger than an area which is to be dressed by said dresser.

6. (Amended) A polishing apparatus for polishing a workpiece, said polishing apparatus comprising:

a polishing table having a polishing surface;

a top ring for holding a workpiece and pressing the workpiece against said polishing surface;

a dresser for dressing said polishing surface;

a sensor for observing a property of said polishing surface on said polishing table while said polishing surface is being dressed by said dresser; and

a determination device for comparing an initial property of said polishing surface which is observed by said sensor with a property of said polishing surface (which is observed by said sensor after said polishing surface is dressed by said dresser) and determining when to replace a component of said polishing surface based on a result of the comparison between the initial property and the property of the polishing surface which is observed after said polishing surface is dressed.

Please add new claims 8-22 as follows:

8. (New) The polishing apparatus according to claim 6, wherein said sensor is for observing irregularity or undulation of said polishing surface.

9. (New) The polishing apparatus according to claim 6, further comprising a display device for displaying the property of said polishing surface observed by said sensor.

10. (New) The polishing apparatus according to claim 6, wherein said sensor is vertically movable independently of said top ring or said dresser.

11. (New) The polishing apparatus according to claim 6, wherein said sensor is to observe a property of said polishing surface over an area that is larger than an area which is to be dressed by said dresser.

12. (New) The polishing apparatus according to claim 2, further comprising a display device for displaying the property of said polishing surface observed by said sensor.

13. (New) The polishing apparatus according to claim 12, wherein said sensor is vertically movable independently of said top ring or said dresser.

14. (New) The polishing apparatus according to claim 13, wherein said sensor is to observe a property of said polishing surface over an area that is larger than an area which is to be dressed by said dresser.

15. (New) The polishing apparatus according to claim 12, wherein said sensor is to observe a property of said polishing surface over an area that is larger than an area which is to be dressed by said dresser.

16. (New) The polishing apparatus according to claim 2, wherein said sensor is vertically movable independently of said top ring or said dresser.

17. (New) The polishing apparatus according to claim 16, wherein said sensor is to observe a property of said polishing surface over an area that is larger than an area which is to be dressed by said dresser.

18. (New) The polishing apparatus according to claim 2, wherein said sensor is to observe a property of said polishing surface over an area that is larger than an area which is to be dressed by said dresser.

19. (New) The polishing apparatus according to claim 3, wherein said sensor is vertically movable independently of said top ring or said dresser.

20. (New) The polishing apparatus according to claim 19, wherein said sensor is to observe a property of said polishing surface over an area that is larger than an area which is to be dressed by said dresser.

21. (New) The polishing apparatus according to claim 3, wherein said sensor is to observe a property of said polishing surface over an area that is larger than an area which is to be dressed by said dresser.

22. (New) The polishing apparatus according to claim 4, wherein said sensor is to observe a property of said polishing surface over an area that is larger than an area which is to be dressed by said dresser.

